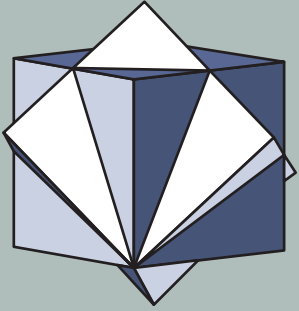




GEORG-AUGUST-UNIVERSITÄT
GÖTTINGEN



30th DGKK Workshop Göttingen

10th – 11th December 2015

Organized by IV. Physikalisches Institut, Georg-August-Universität Göttingen

with support from



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Session Overview

Thursday, 10th December

12:00 - 13:00	Registration and Welcome Snack	
13:00 - 14:00	Session 1 HS 2 Invited	
14:00 - 16:00	Session 2A HS 3 Quantum dots and laser structures	Session 2B HS 4 III/V on Silicon
16:00 - 16:30	Coffee Break sponsored by 	
16:30 - 18:30	Session 3A HS 3 Structures for electronic devices	Session 3B HS 4 Semipolar and bulk III-Nitrides
Workshop Dinner sponsored by 		

Friday, 11th December

9:15 - 10:00	Session 4 HS 2 Invited	
10:00 - 11:00	Session 5A HS 3 Nanowires I	Session 5B HS 4 Impurities
11:00 - 11:30	Coffee Break sponsored by 	
11:30 - 13:30	Session 6A HS 3 Nanowires II	Session 6B HS 4 Growth and in-situ monitoring
Closing and Light Lunch		

Scientific Program

Session 1: Invited

Thursday, 13:00 - 14:00 (HS 2)

13:00	A. Rizzi	Welcome
13:15	U. Steegmüller	LEDs and Laser Diodes: Today's and Future Trends in Lighting

Session 2A: Quantum dots and laser structures

Thursday, 14:00 - 16:00 (HS 3)

14:00	D. Quandt	Submonolayers with antimony and 1.3 μm low-density quantum dots
14:20	C. Clausen	InGaAs-quantum dots in the telecom wavelength range combined with a VCSEL as excitation source
14:40	S. Hepp	Far-field and quality factor optimized photonic crystal cavities for high collection efficiencies in quantum optical applications
15:00	A. Kaganskiy	Advanced Cathodoluminescence Lithography for the Deterministic Nanofabrication of Quantum Light Sources
15:20	R. Bek	AlGaInP disk laser design for enhanced pump efficiency
15:40	S. Seifert	Revised refractive index and absorption of InGaAsP lattice-matched to InP in transparent and absorption IR-region

Session 2B: III/V on Silicon

Thursday, 14:00 - 16:00 (HS 4)

14:00	K. Werner	Sub monolayer CVD of TBP on Si (001)
14:20	C. Koppka	Reduction of rotational twin formation in GaP epilayers on Si(111) for improved III-V nanowire growth
14:40	O. Supplie	Single-domain GaP heteroepitaxy on Arsenic-modified Si(100)
15:00	A. Paszuk	Silicon p-n junctions prepared by group-V in-diffusion in CVD ambient
15:20	L. Grieger	Quantitative domain orientation analysis of GaN/Er ₂ O ₃ grown on vicinal Si(001)
15:40	S. Brückner	In situ study of Ge (100) step and domain formation in MOVPE under influence of III-V residuals

Session 3A: Structures for electronic devices

Thursday, 16:30 - 18:30 (HS 3)

16:30	A. Wille	Electro-optic Modulator based on 2DEG-containing AlN/ GaN superlattice structures
16:50	T. Wernicke	Exploring the limits of n- and p-type doping of Al _x Ga _{1-x} N with high aluminum mole fractions $x > 80\%$
17:10	J. Hennig	Enhancement-mode operation of AlInN/AlN/GaN HEMTs by magnesium doped GaN capping layers
17:30	B.-J. Godejohann	AlN/GaN HEMTs for High Frequency Power Electronics
17:50	S. Breuer	Carbon Doping using Pentane for GaN-on-Si HEMTs with High Vertical Breakdown Voltage
18:10	S. Fleischmann	AlGaIn layers grown by HVPE

Session 3B: Semipolar and bulk III-Nitrides

Thursday, 16:30 - 18:30 (HS 4)

16:30	B. Weinert	Entwicklung von 2"-FS-GaN-Substraten für den Telekommunikationssektor im Rahmen des BMBF-Projektes "TeleGaN"
16:50	F. Scholz	Planar semipolar (11-22) green InGaIn/GaN LEDs grown on Patterned Sapphire Substrates
17:10	P. Horenburg	Strain dependence of indium incorporation in m-oriented GaInN/GaN multi quantum well structures
17:30	M. Caliebe	Influence of trench period and depth on MOVPE grown (11-22) GaN on patterned r-plane sapphire substrates
17:50	M. Bickermann	Bulk AlN Substrates for Deep-UV Optoelectronic Applications
18:10	E. Gridneva	Hydride Vapor Phase-Epitaxy of iron-doped GaN layers with diameters up to 100 mm

Session 4: Invited

Friday, 9:15 - 10:00 (HS 2)

9:15	D. Car	Rationally Designed Single-Crystalline Nanowire Networks
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Session 5A: Nanowires I

Friday, 10:00 - 11:00 (HS 3)

10:00	T. Rieger	The route towards complex nanowire geometries
10:20	T. Wierzkowski	Growth Evolution of Lateral InAs Nanowires on Si (110)
10:40	A. Nägelein	Electrical characterization and modelling of p-GaAs nanowires by MT-STM

Session 5B: Impurities

Friday, 10:00 - 11:00 (HS 4)

10:00	S. Bauer	Optical Characterization of GaN:Fe
10:20	M. Feifel	Impact of the III-V MOVPE Environment on the Minority Carrier Lifetime in Silicon
10:40	D. Lackner	Employing Power Dependent Relative Photoluminescence for MOVPE Process Control

Session 6A: Nanowires II

Friday, 11:30 - 13:30 (HS 3)

11:30	M. Steidl	Growth kinetics of GaP-nanowires employing TBP and TMGa
11:50	H. Potts	Growth of twin-free InAs _{1-x} Sb _x nanowires using MBE
12:10	O. Rettig	GaN-Nanowires for Sensor Applications
12:30	C. Tessarek	Self-catalyzed and Si-induced growth of vertically aligned InN nanorods by MOVPE
12:50	C. Blumberg	Morphology control of self-catalyzed GaN-microrods on silicon grown by MOVPE
13:10	H. Zhou	Density reduction of large hexagonal pyramidal structures in MOVPE selective area growth of 3D GaN column arrays

Session 6B: Growth and in-situ monitoring

Friday, 11:30 - 13:30 (HS 4)

11:30	M. Heuken	Blue LED manufacturing optimization based on a MOCVD growth parameter sensitivity study
11:50	T. Wurm	InGaN QW growth on c-plane off-cut substrates
12:10	C. Berger	Analysis of in-situ reflectance measurements during growth of nitride-based Bragg reflectors
12:30	F. Brunner	Advanced in-situ control for GaN-based electronic devices
12:50	A. Tonkikh	Molecular Beam Epitaxy of Large Scale Hexagonal-BN on Sapphire(0001)
13:10	B. Jenichen	Structure of Fe ₃ Si/Al/Fe ₃ Si metal thin film stacks

Session 7: Closing

Friday, 13:40 - 13:50 (HS 4)